

**RADIATION SENSITIVE RESIN COMPOSITION FOR FORMING INSULATION  
FILM OF ORGANIC EL DISPLAY ELEMENT, INSULATION FILM FORMED FROM  
THE SAME AND ORGANIC EL DISPLAY ELEMENT**

**Patent number:** JP2002182380  
**Publication date:** 2002-06-26  
**Inventor:** SUZUKI MASAMUTSU; SASAKI HIROBUMI;  
NISHIMURA ISAO; NIWA KAZUAKI  
**Applicant:** JSR CORP  
**Classification:**  
**- international:** G03F7/022; C08K5/28; C08L101/06; G03F7/032;  
G03F7/038; H05B33/14; H05B33/22  
**- european:**  
**Application number:** JP20000379680 20001214  
**Priority number(s):**

**Abstract of JP2002182380**

**PROBLEM TO BE SOLVED:** To provide a radiation sensitive resin composition for forming an insulation film of an organic EL(electroluminescent) element capable of forming a through hole or a U-shaped recess, excellent in flattening performance and having high transparency and high resistance to a resist removing solution and to provide an insulation film of an organic EL element formed from the composition and an organic EL display element with the insulation film.

**SOLUTION:** The composition contains (a) an epoxy-containing alkali-soluble resin and (b) a 1,2-quinonediazido compound. The insulation film is formed from the composition. The organic EL display element has the insulation film.

---

Data supplied from the **esp@cenet** database - Worldwide

**BEST AVAILABLE COPY**